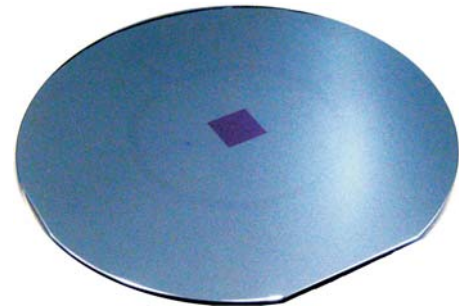


# LARGE-AREA

## NANO-HOLE AND PILLAR PATTERNS

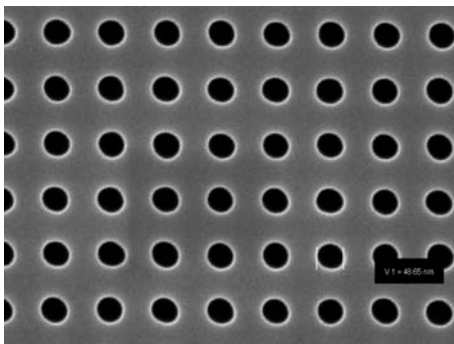
*high-quality arrays for affordable prices*

- Proprietary e-beam process for efficient writing
- Area: 1 cm<sup>2</sup> - 10 cm<sup>2</sup>
- Feature diameter: 30 nm and up
- Flexible Design:
  - Customer specified pattern pitch (period)
    - Minimum pitch for holes: 70 nm
    - Minimum pitch for pillars: 100 nm
  - Customer specified aspect ratio (height/diameter)
    - For holes: up to 3
    - For pillars: up to 4
- Substrate size 4" Si (dicing optional)
- Anti-stick coating available

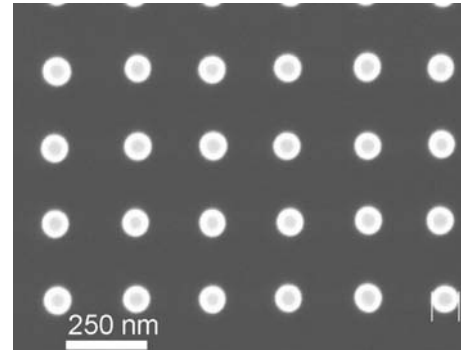


### Applications

- NIL process development
- Photonic patterns
- Self-assembly templates
- Magnetic nanostructures
- Nanoparticle production
- Epitaxial growth



*Nanoholes - pitch 100 nm - depth 100 nm*



*Nanopillars - pitch 250 nm - height 200 nm*

